

1 **Water Monolayers: An Overlooked Loss Mechanism in Mid-Infrared Photonics –**
2 **Supplement**

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10 **S1. WAVEGUIDE GEOMETRIES**

11 The slot waveguide, whose schematic cross section and top view can be observed in Fig.
 12 S1(a), was designed for methane detection at $\lambda = 3.27 \mu\text{m}$ on a silicon-on-insulator (SOI)
 13 platform and is described in¹. The designed dimensions are $H = 500 \text{ nm}$, $W = 550 \text{ nm}$,
 14 $s = 150 \text{ nm}$. The buried-oxide (BOX) layer has a thickness $H_{\text{BOX}} = 3 \mu\text{m}$. The geometry
 15 of the silicon nitride (SiN) suspended waveguide with micro-structured lateral cladding is
 16 illustrated in Fig. S1(b). The sample designed at $\lambda = 3.27 \mu\text{m}$ is a W3 waveguide, with
 17 lattice period $a = 1.3 \mu\text{m}$ and hole diameter $d = 1.1 \mu\text{m}$, whereas the one working at
 18 $\lambda = 4.35 \mu\text{m}$ is a W5 featuring $a = 2 \mu\text{m}$ and $d = 1.55 \mu\text{m}^2$. In both cases, the thicknesses
 19 of the guiding layer and the undercut are $H = 500 \text{ nm}$ and $H_u > 30 \mu\text{m}$, respectively.

20 Representative SEM images of the SOI slot and the SiN suspended waveguide are shown
 21 in Fig. S2(a)–(b). By analyzing the picture of the slot waveguide (Fig. S2(a)), several
 22 deviations from the ideal geometry are observed, including over-etching down to the BOX
 23 layer, and slightly angled Si sidewalls, resulting in narrowing of the slot towards the bottom
 24 of the structure. These are accounted for in the waveguide model we describe in Sec. S4.

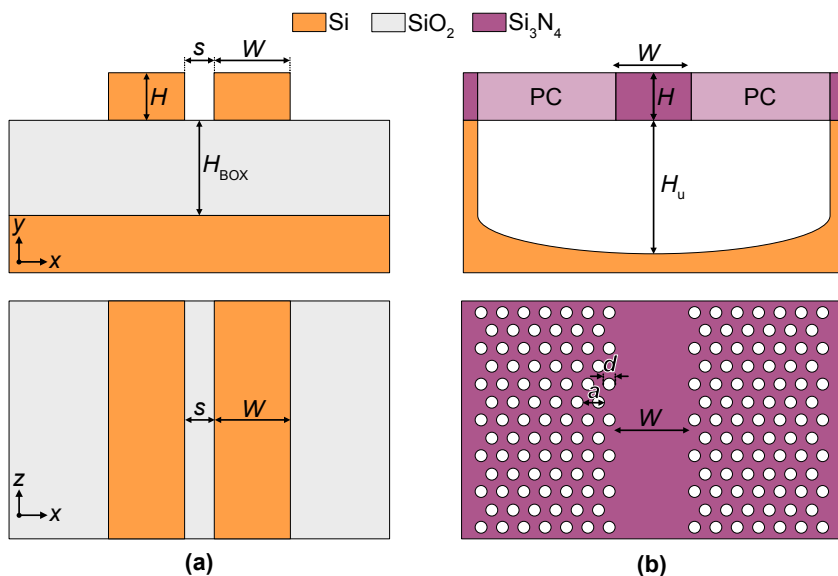


FIG. S1. Schematic cross-sectional and top views of the (a) silicon slot and (b) silicon nitride suspended waveguides analyzed in this work. Note that the representations are not at true scale.

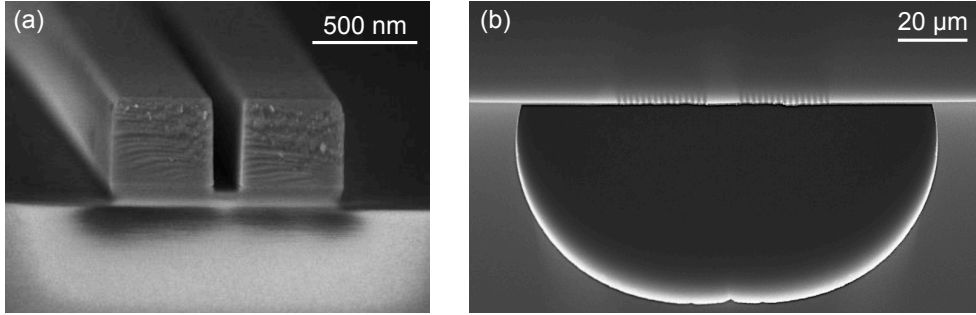


FIG. S2. SEM pictures of the (a) silicon slot and (b) silicon nitride suspended waveguides.

25 S2. EXTENDED EXPERIMENTAL DATA

26 Figure S3 shows a representative time-resolved measurement of the slot-waveguide loss,
 27 with the corresponding relative humidity (RH) color-encoded. At each RH step, we acquired
 28 multiple traces that capture the approach to a local steady state. As shown in the inset,
 29 the loss values at a given set point are well described by an exponential model. For our
 30 analysis, we used, at each RH set point, the value obtained by extrapolating the exponential
 31 fit to 99% of the steady-state response. This choice removes minor artifacts due to small
 32 variations in acquisition timing across steps. The discrepancy between the last recorded
 33 point and the extrapolated saturation value is small ($< 2\%$ of the value), indicating that
 34 the extrapolation introduces negligible bias.

35 Figure S4 presents the full set of excess-loss measurements for both the slot and suspended
 36 waveguides, with vertical scales adjusted to the respective data ranges. Repeated measure-
 37 ments were performed for the slot waveguide to assess the repeatability of the procedure
 38 and reproducibility of the results, yielding a standard deviation of only $\sigma \approx 0.17$ dB/cm.
 39 The same experimental protocol was applied to the SiN membrane waveguides, lending
 40 confidence to the consistency of the results.

41 S3. CONTACT-ANGLE MEASUREMENTS

42 To assess the wettability of the investigated material surfaces, sessile drop measurements
 43 were performed directly on the fabricated chips, as close as possible to the waveguide struc-
 44 tures. A deionised water droplet with a volume of $7 \mu\text{l}$ was deposited using a pipette po-
 45 sitioned approximately 2.5 mm above the surface. The results, shown in Fig. S5, indicate

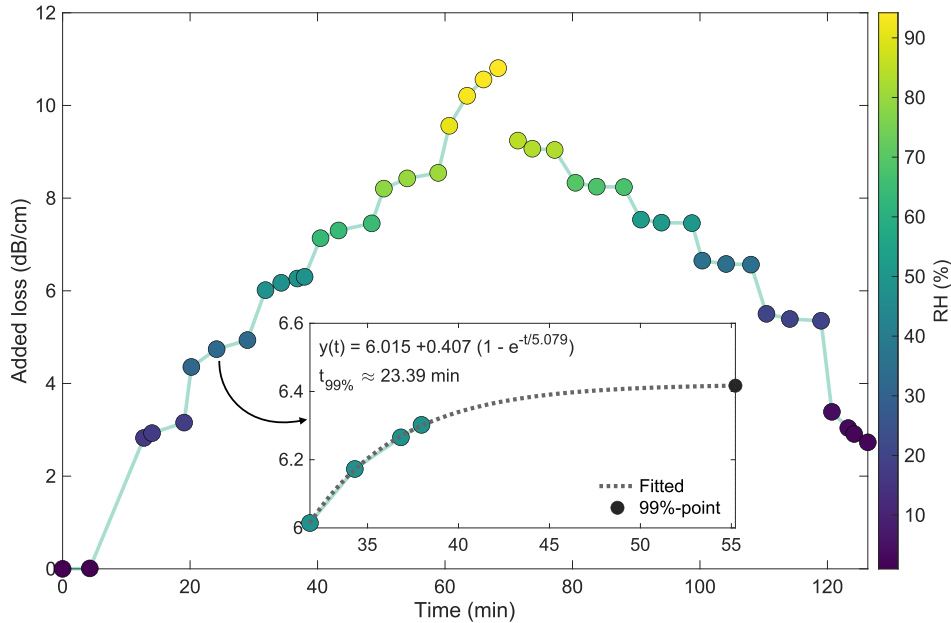


FIG. S3. Time-resolved measurements of the slot waveguide. Relative humidity is color-encoded. The inset shows the exponential model fitted to the loss values within one step.

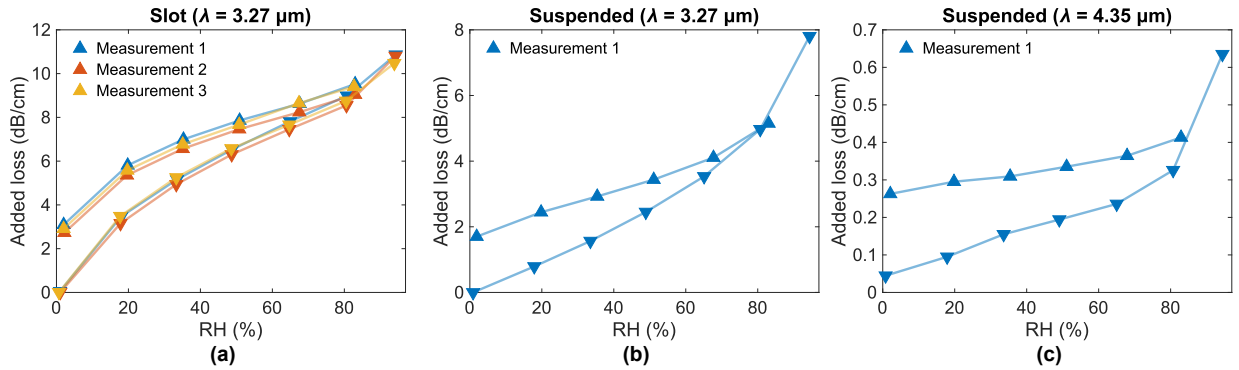


FIG. S4. Complete set of measurements of the (a) slot and (b,c) suspended waveguides, operating at (b) $\lambda = 3.27 \mu\text{m}$ and (c) $\lambda = 4.35 \mu\text{m}$. Good measurement repeatability is evident from the slot results.

46 that silicon exhibits strongly hydrophobic behaviour, with an average contact angle of 94.2°
 47 across different measurements. Silicon nitride, in contrast, is moderately hydrophobic, with
 48 an average contact angle of 65.1° . As a reference, measurements on a SiO_2 glass slide show
 49 significantly higher hydrophilicity, with an average contact angle of 40.4° , in good agree-
 50 ment with literature values and markedly lower than those of Si and $\text{SiN}^{3,4}$. It should be

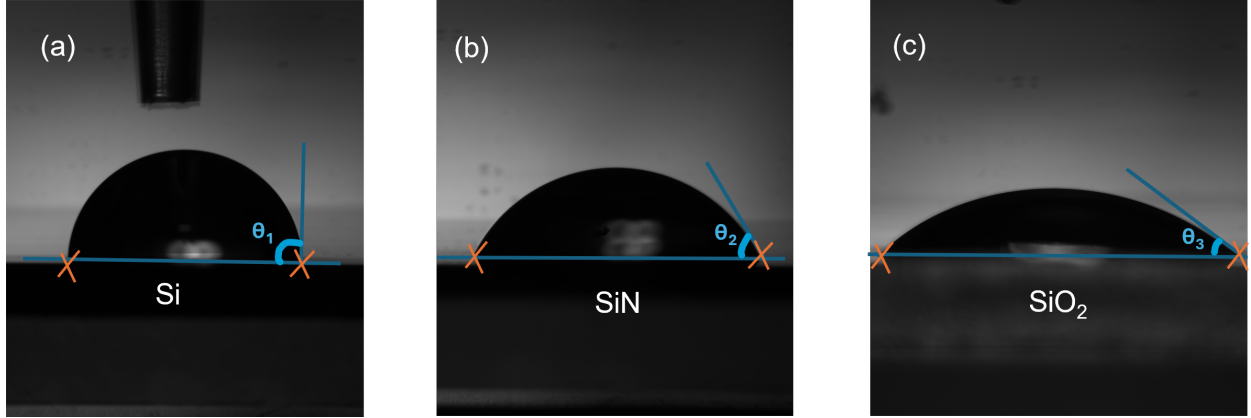


FIG. S5. Representative side-view images of water droplets deposited on (a) Si, (b) SiN, and (c) SiO₂ surfaces for contact angle analysis. The baseline and tangent at the three-phase contact point are used to determine the contact angle θ , as illustrated. Variations in the measured angles $\theta_1 = 94^\circ$, $\theta_2 = 65^\circ$, and $\theta_3 = 40^\circ$ reflect differences in surface wettability.

51 noted that this technique probes only the top surface of the chips; the wettability of vertical
 52 sidewalls and buried interfaces is inferred from the fabrication processes.

53 S4. SIMULATION DETAILS

54 Figure S6(a) shows the modeled slot waveguide cross-section used in the numerical sim-
 55 ulations (Ansys Lumerical), incorporating the main fabrication deviations observed in SEM

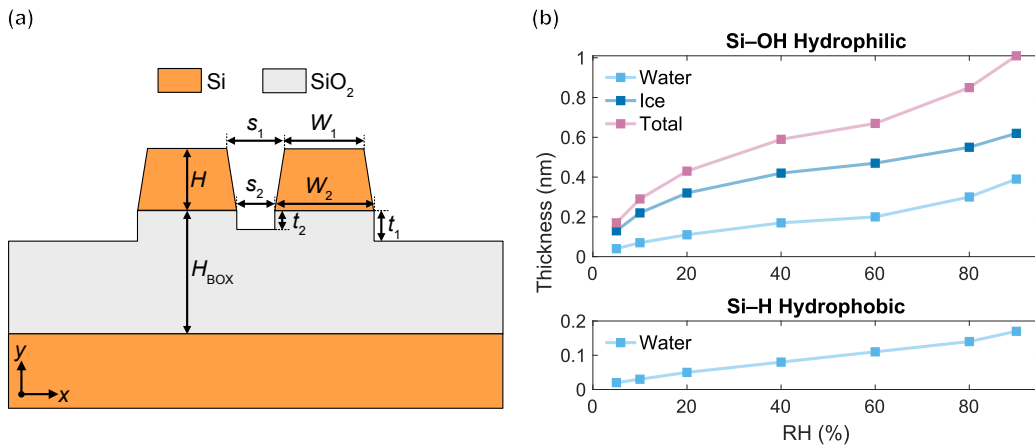


FIG. S6. (a) Slot waveguide cross section as modelled in numerical simulations. (b) Model for the adsorbed water layers employed in simulations based on data published in Ref.⁵.

56 images, such as the example in Fig. S2(a). Based on this analysis, the following dimensions
57 were used: $W_1 = 550$ nm, $W_2 = 560$ nm, $s_1 = 150$ nm, $s_2 = 140$ nm, $t_1 = 100$ nm, and
58 $t_2 = 30$ nm. The total silicon and buried oxide thicknesses were kept at $H = 500$ nm and
59 $H_{\text{BOX}} = 3$ μm , respectively.

60 To model humidity effects, ice- and liquid-like water layers were introduced on all air-
61 exposed surfaces. The structure and thickness of these layers as a function of relative
62 humidity as extracted from⁵ is reproduced in Fig. S6(b).

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